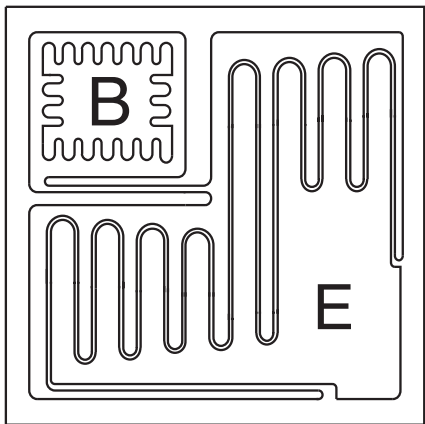


**PROCESS DETAILS**

Process	EPITAXIAL BASE
Die Size	195 X 195 MILS
Die Thickness	12 MILS
Base Bonding Pad Area	29 X 29 MILS
Emitter Bonding Pad Area	61 X 35 MILS
Top Side Metalization	Al - 30,000Å
Back Side Metalization	Ti/Ni/Au - 6,000Å

**GEOMETRY**



BACKSIDE COLLECTOR R0

**GROSS DIE PER 5 INCH WAFER**

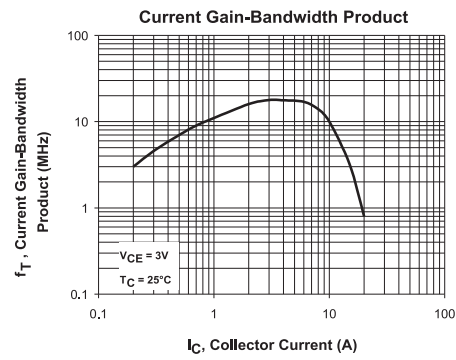
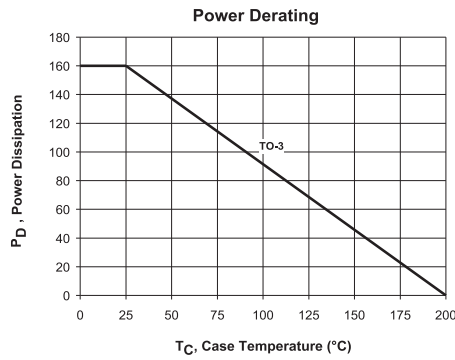
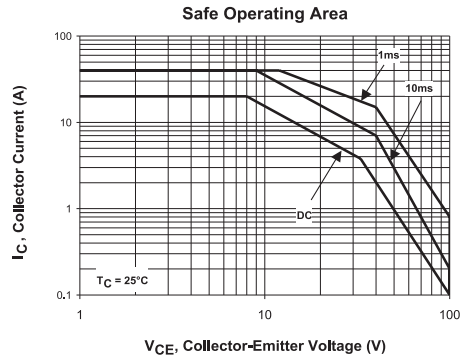
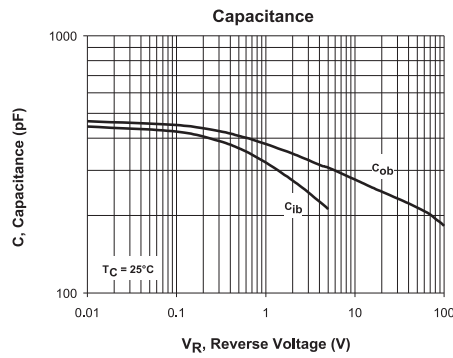
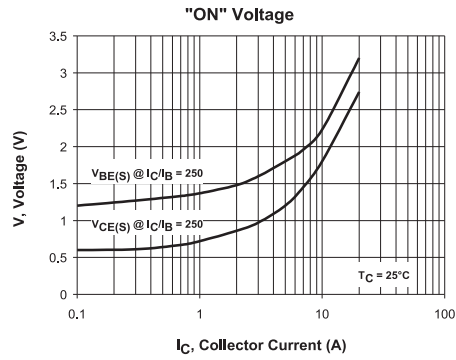
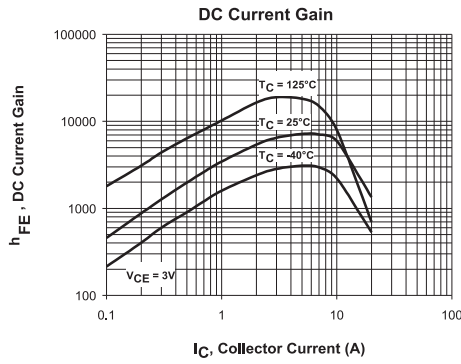
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**PRINCIPAL DEVICE TYPES**

- MJ11011 2N6285
- MJ11013 2N6286
- MJ11015 2N6287

145 Adams Avenue  
Hauppauge, NY 11788 USA  
Tel: (631) 435-1110  
Fax: (631) 435-1824  
www.centrasemi.com

R3 (1-August 2002)



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